

Substitute for form 1449/PTO (Revised 07/2007)  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> <i>(Use as many sheets as necessary)</i>				<b>Complete if Known</b>	
				International Appl. No.	PCT/US2004/042706
				International File Date	December 20, 2004
				Application Number	10/583,570
				First Named Inventor	DeSimone
				Art Unit	1617
				Examiner Name	Sheikh, H.
Sheet	1	of	1	Attorney Docket Number	035052/338899

**U. S. PATENT DOCUMENTS**

Examiner Initials*	Cite No.	<u>Document Number</u> Number - Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages of Relevant Figures Appear
	196	US-4,818,801	04-04-1989	Rice, D.E., <i>et al.</i>	
	197	US-2002/0172895	11-21-2002	Breen, T.L., <i>et al.</i>	

**FOREIGN PATENT DOCUMENTS**

Examiner Initials	Cite No.	<u>Foreign Patent Document</u> Country Code - Number Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	English Language Translation Attached

**OTHER DOCUMENTS**

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	English Language Translation Attached
	198	BAILEY, T., <i>et al.</i> "Step and Flash Imprint Lithography: Template Surface Treatment and Defect Analysis," <i>J. Vac. Sci. Technol. B</i> , 2000, pp. 3572-3577, Vol. 18(6).	
	199	HIRAI, Y., <i>et al.</i> , "Mold Surface Treatment for Imprint Lithography," <i>Journal of Photopolymer Science and Technology</i> , 2001, pp. 457-462, Vol. 14(3).	

Examiner Signature		Date Considered	
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\*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.